

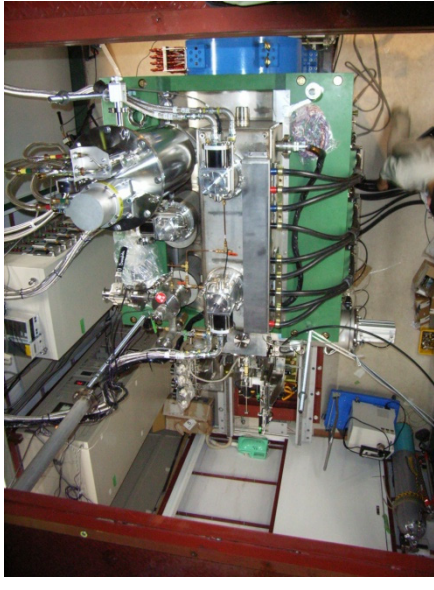
Recent THE RIKEN 28GHz SC-ECRIS Result

Y. Higurashi[#], J. Ohnishi, K. Ozeki, H. Haba, M. Fujimaki,
M. Kidera, M. Komiyama and O. Kamigaito, RIKEN

T. Aihara, M. Tamura, A Uchiyama, SHI

Milestone

- 2007 Design start
- 2008 Construction start
- 2009 First beam with 18GHz
- 2010 Test experiment with 18GHz
Install the ion source in the new
IS room for new injector system
- 2011 Installation of 28GHz gyrotron
First beam with 28GHz



Production of Xe and U beam with 28GHz
at the RF power <2kW

Contents of presentation

- ❑ Introduction
- ❑ Heat load problem (GM-JT)
- ❑ Gyrotron and its stabilization.
- ❑ Beam production
(Xe U intensity emittance)
- ❑ Conclusion and future plan.

New injector system RILAC2

New injector system (2010~)

Requirement (FY2012)

U^{35+} beam production

Sputtering method

$1.5\mu A$

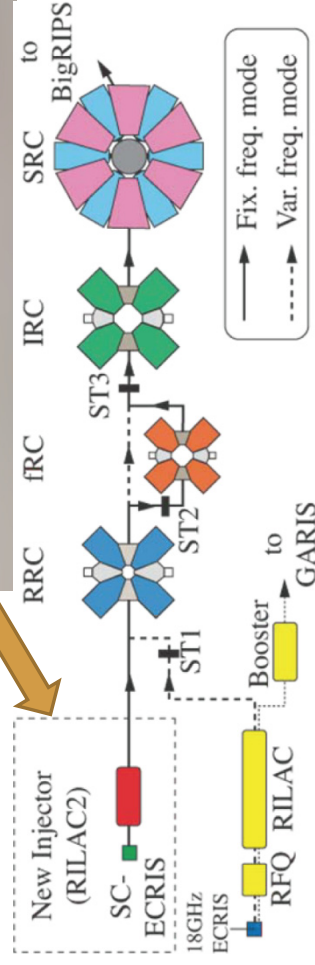
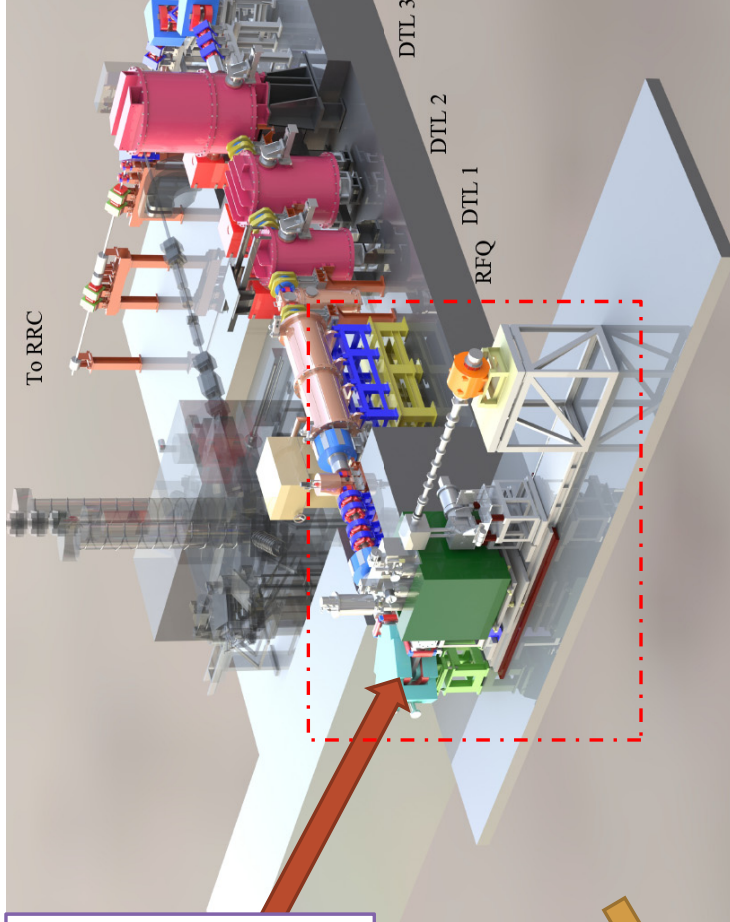
long term operation(> 1month)

$\sim 100\pi mm\ mrad$ ($\sim 90\%$)

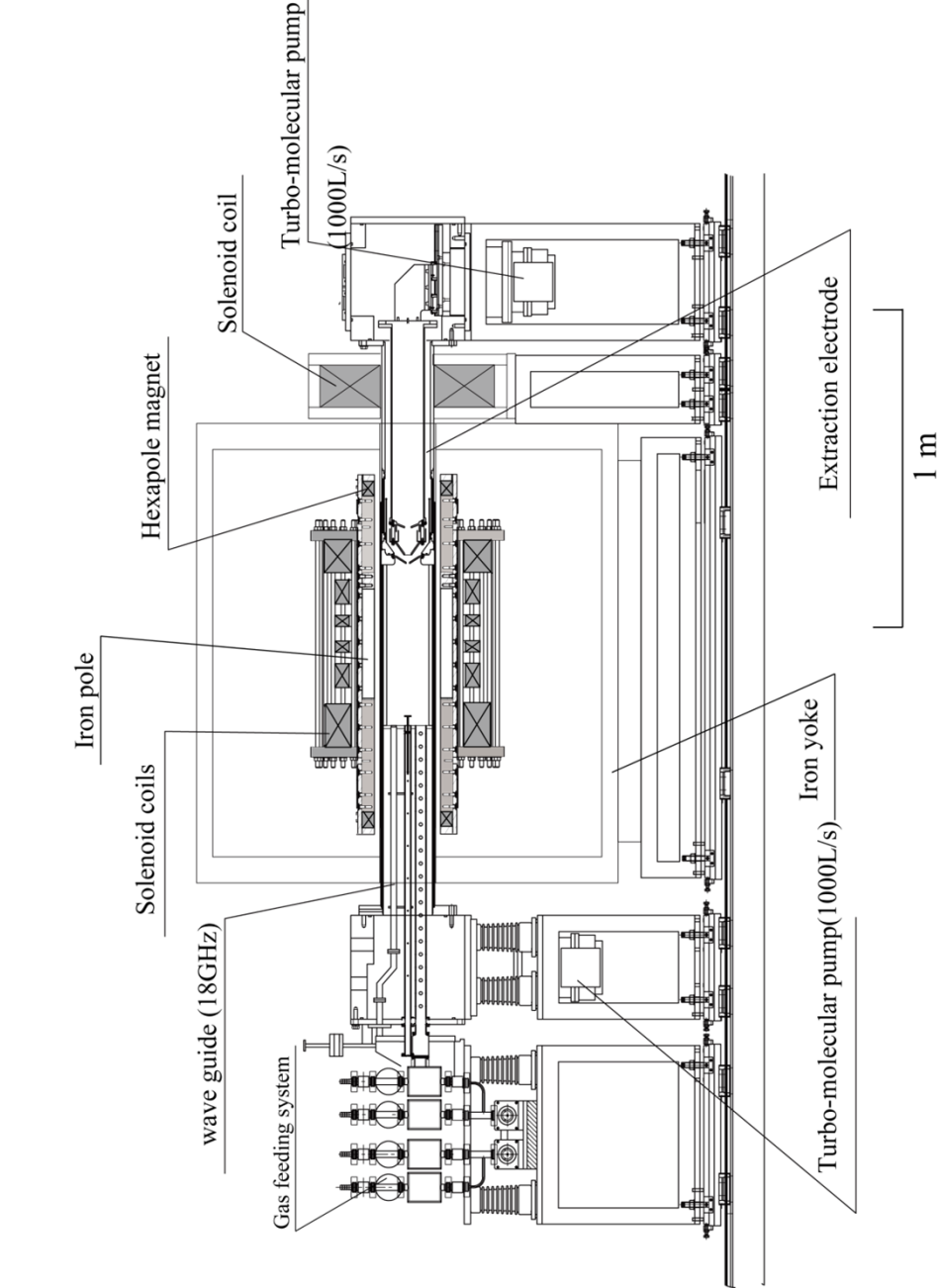
Required charge state

$^{238}U^{35+}$

$^{136}Xe^{20+}$



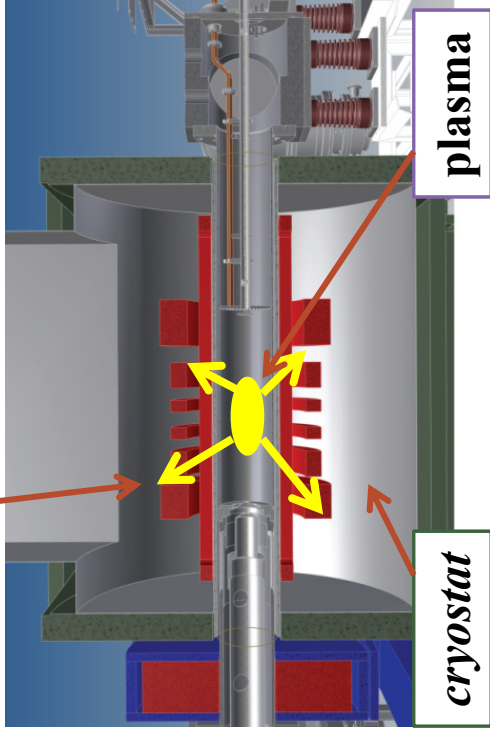
RIKEN 28 GHz SC-ECRIS



- Binj ~ 3.8T
- Bmin < 1T
- Bext ~ 2.3T
- Br ~ 2.1T
- Chamber $\phi 150$ length
- 525mm
- Vext 40kV max
- Micro wave
- 18GHz 1.5kW
- 28GHz 10kW

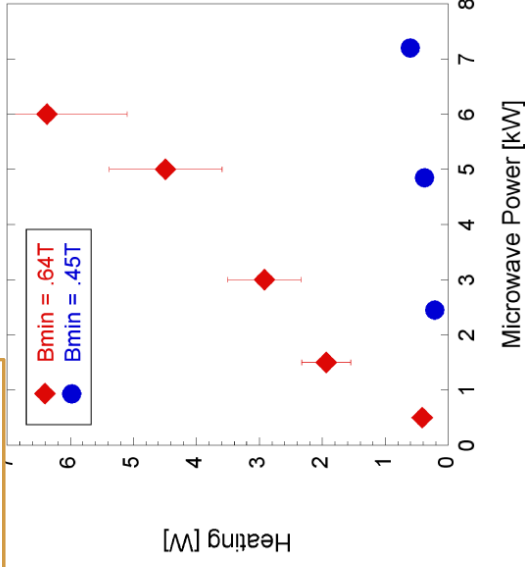
Heat load problem

High energy x-ray (>several 100keV)

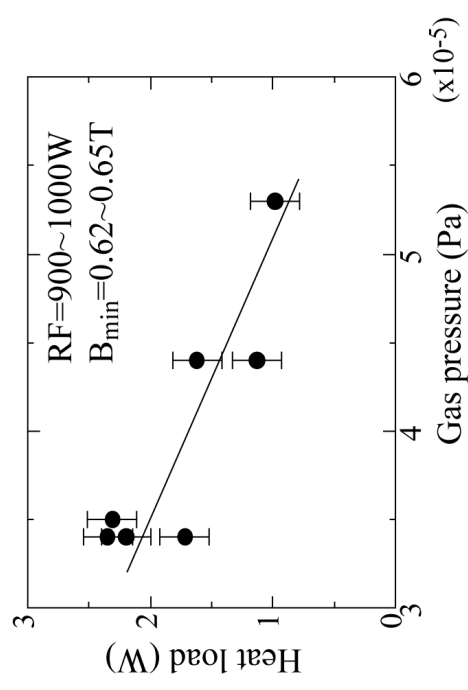


VENUS 28GHz

D. Leitner et al, RSI 79(79)033302



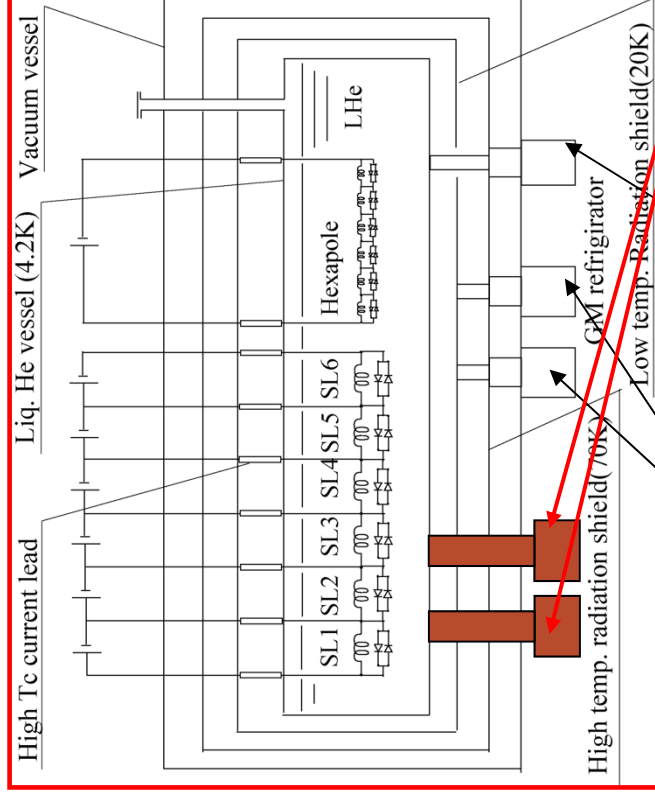
RIKEN SC-ECRIS 28GHz



Y. Higurashi et al, RSI 83, 02A308(2012)

Cryostat

Item	Helium vessel	Low temp. radiation shield	High temp. radiation shield	(W)
Design temp.	4.2 K	20 K	70K	
Radiation	0.005	5.5	40	
Conduction				
Support	0.005	0.3	4	
Port	0.06	1.5	20	
Current lead	0.07	10	64	
total heat load	0.14	17.3	128	



2009.2

2012.4

CG310SC(SUMITOMO)(GM-JT refrig.)

Cooling capacity

4.2W/5.0W@4.2K(50/60Hz)

Electric power consump. 5.1/6.1kW(50/60Hz)

Electric power

Weight

Dimension 700W×520D×1095H

GM refriger. 35W(45K), 6.3W(10K)

GM. Refrig. 50W(43K), 1.0W(4.2K)

New GM-JT

NEW GM-JT 4W@4K



GM-JT refrigerator

GM refrigerators

Iron yoke

RF injection side

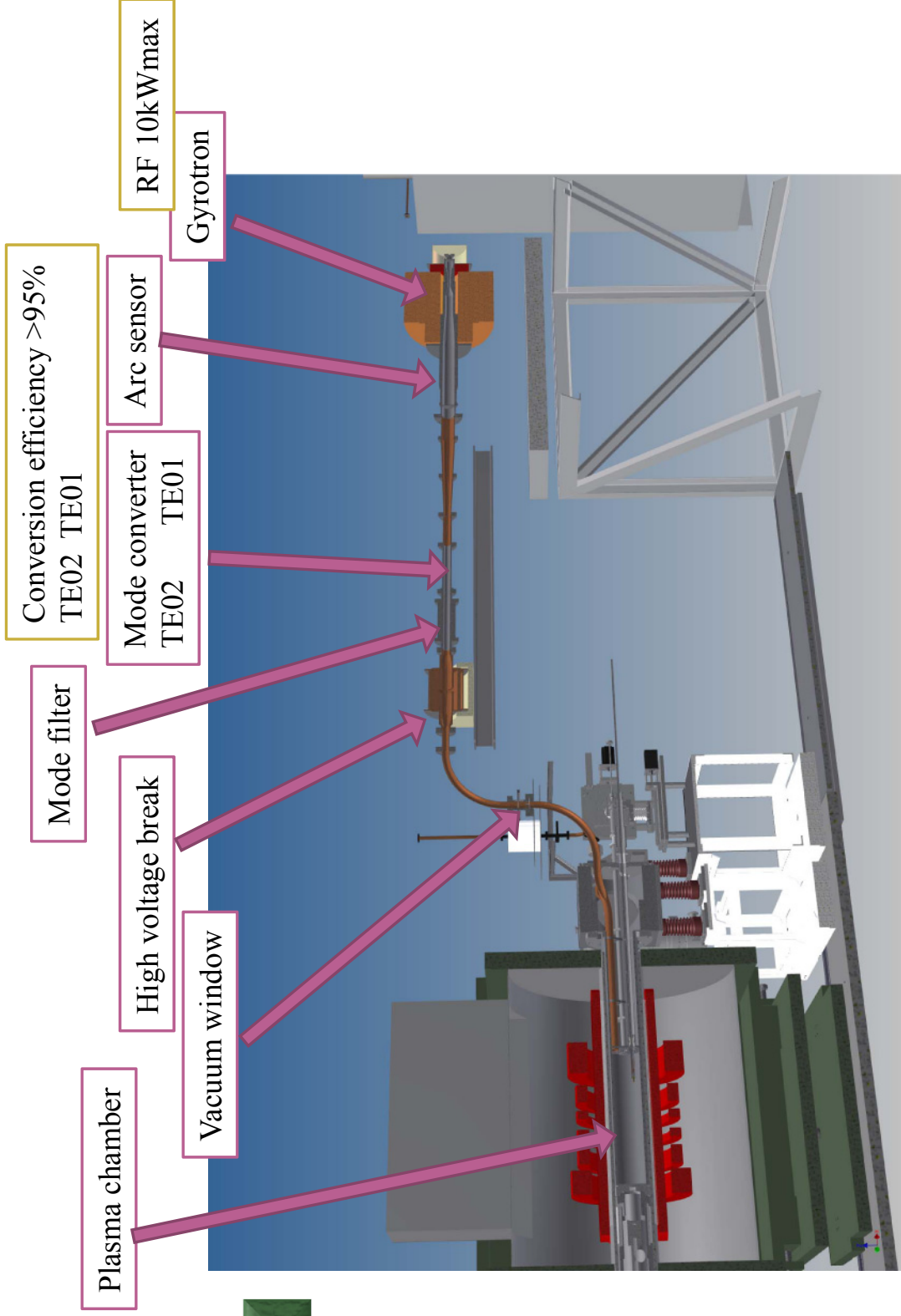
Total 7.8W@4K

Beam extraction side

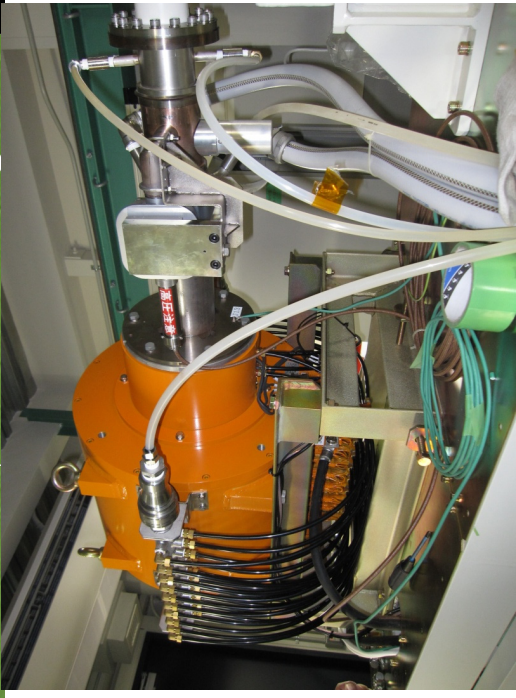
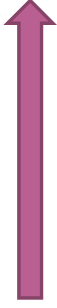
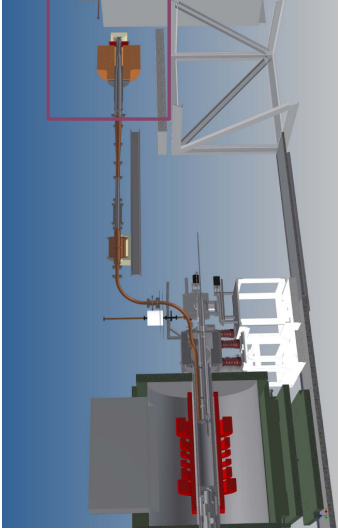
Solenoid coil

28GHz ECRIS + Gyrotron

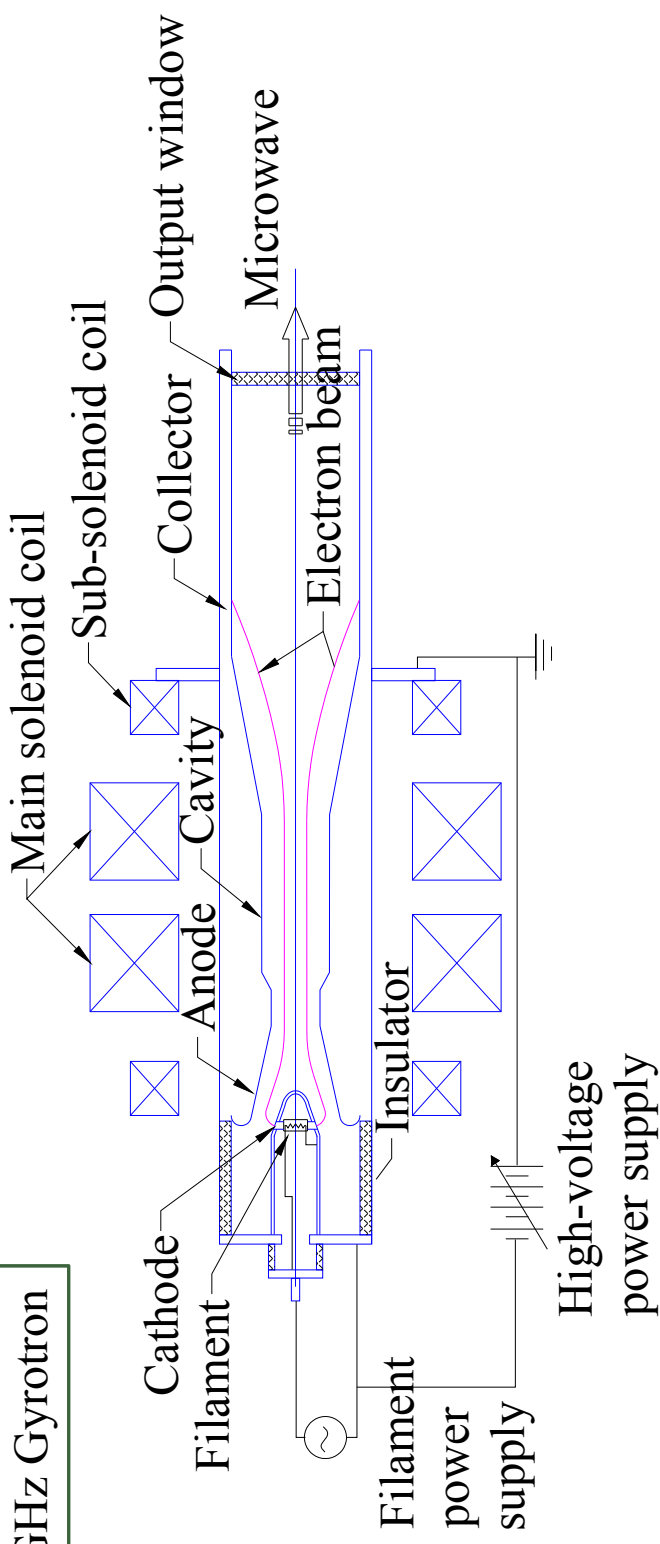
From 2011



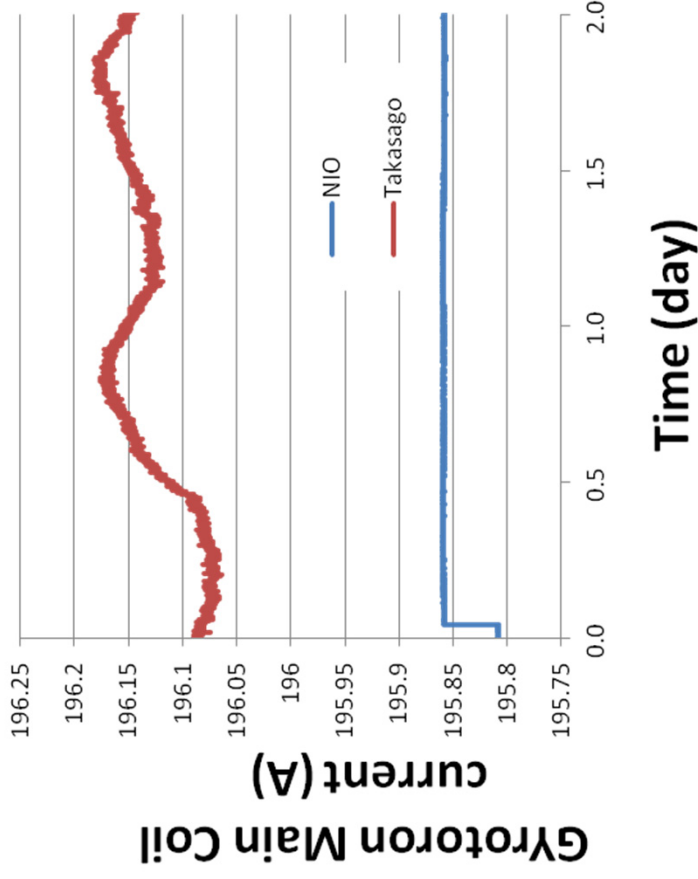
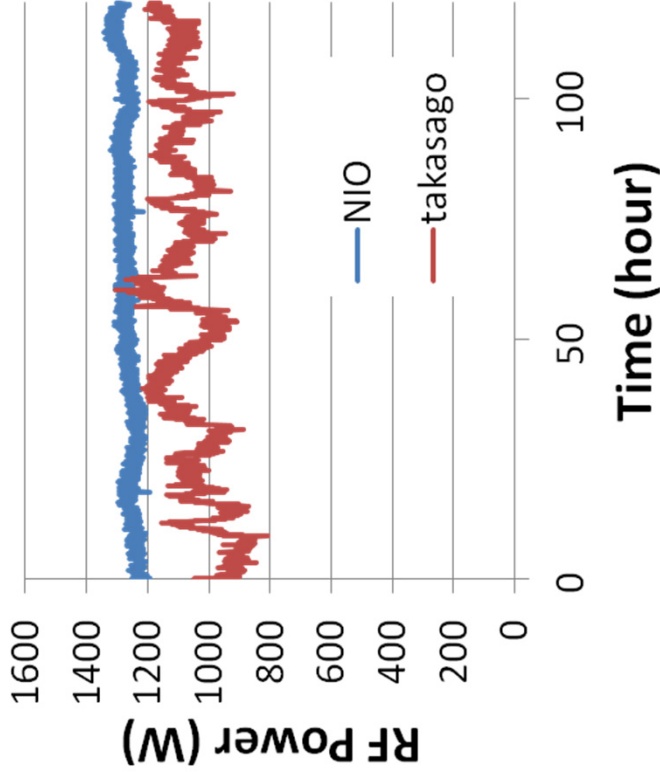
Gyrotron



28GHz Gyrotron

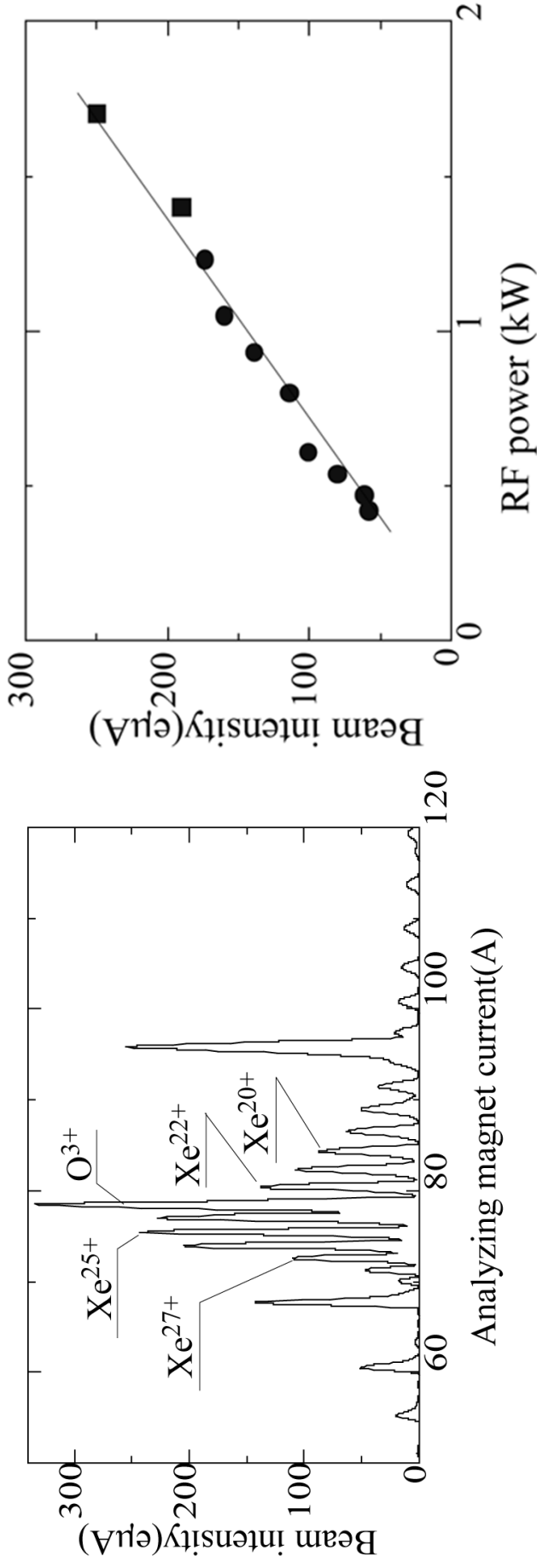


Gyrottron Stability



Main Coil P.S.	Current stability	RF power stability
NIO	10ppm/day	7~8% @1.5kW
Takasago	500ppm/day	20~30% @1.5kW

^{124}Xe beam



Xe^{25+} **250eμA** @1.7kW(28GHz)

B_{inj} 3.2T

B_{min} 0.65T

B_r 1.85T

B_{ext} 1.8T

The extraction voltage 22 kV

The typical gas pressure

$\sim 5 \times 10^{-5}$ Pa

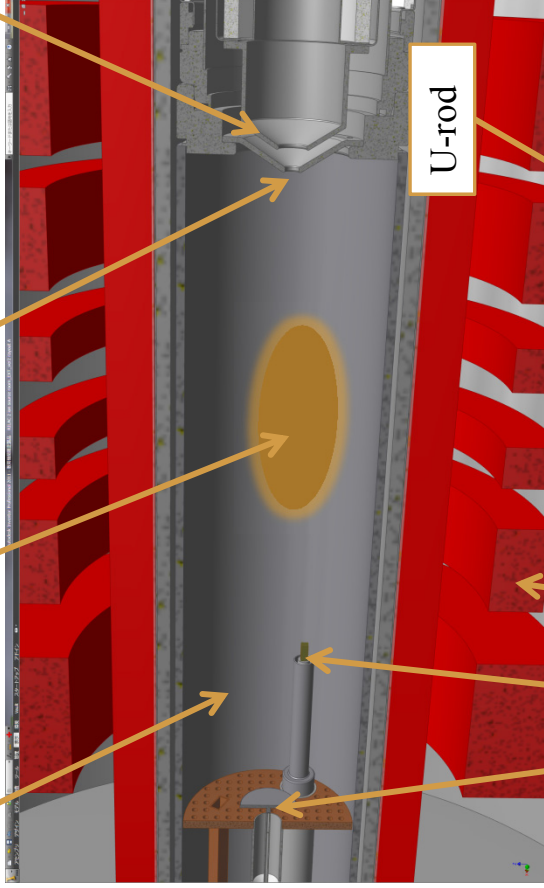
U beam

Extraction electrode

Plasma electrode

ECR zone

Plasma chamber

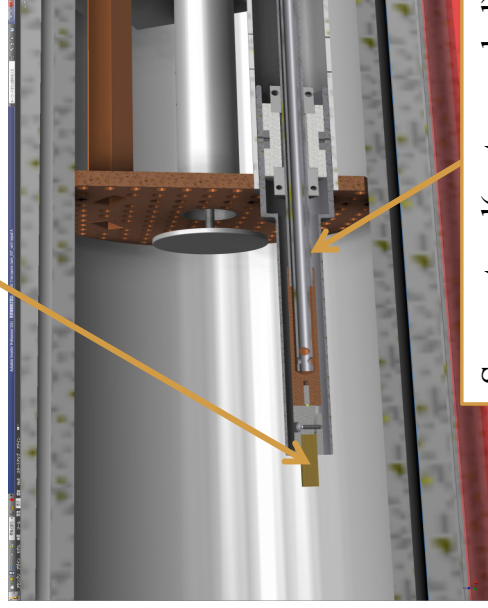


U-rod

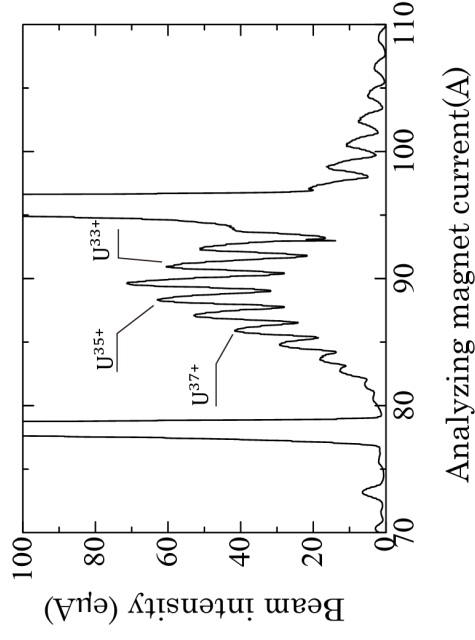
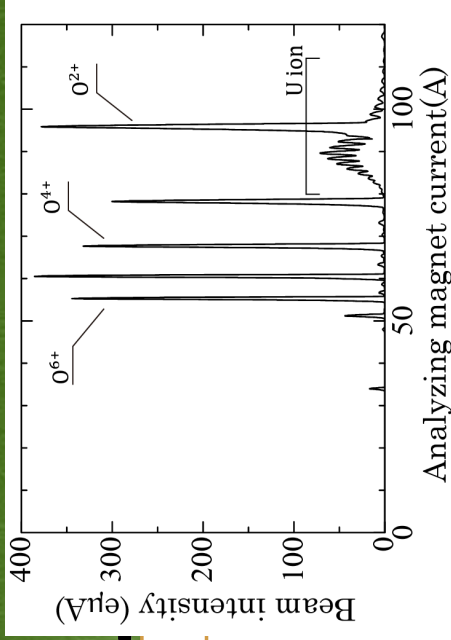
Biased disc

U rod

Sc-solenoid coils



Support rod(water cooled)



U^{35+} **60eμA @2kW(28GHz)**

B_{inj} 3.1T B_{min} 0.65T

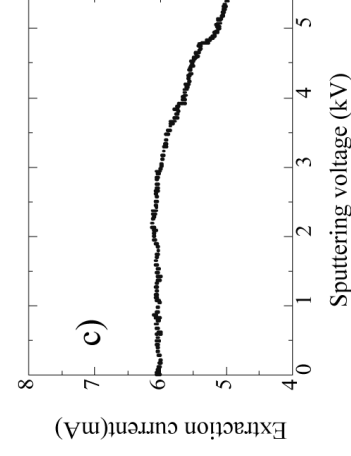
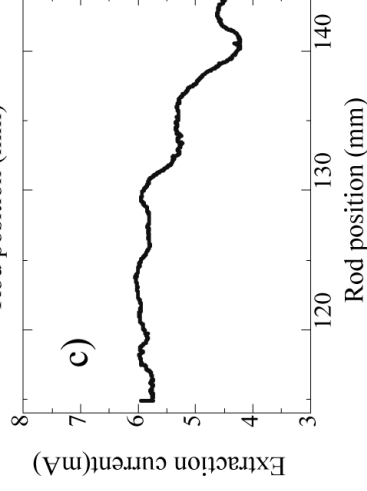
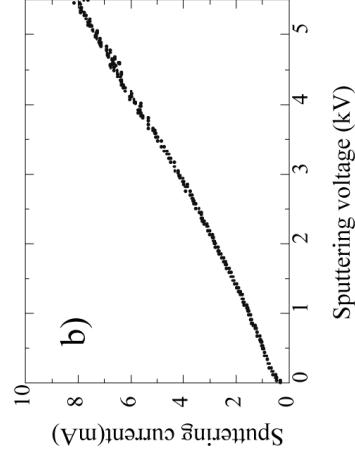
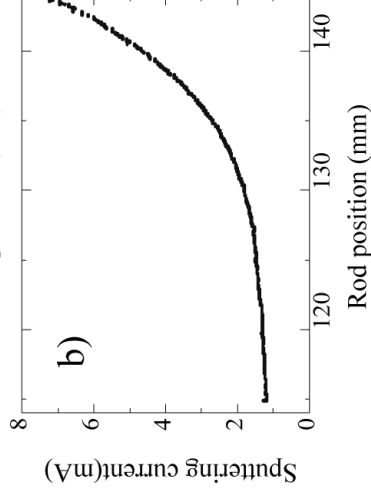
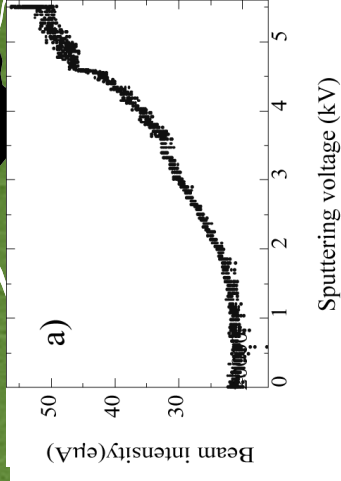
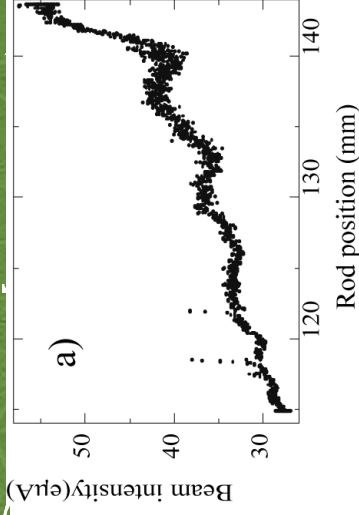
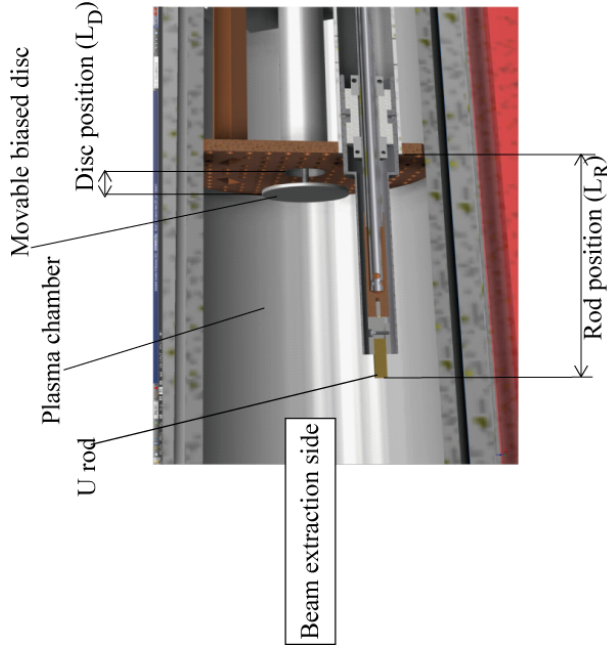
B_r 1.85T B_{ext} 1.8T

The extraction voltage 22 kv.

$3 \sim 5 \times 10^{-5}$ Pa.

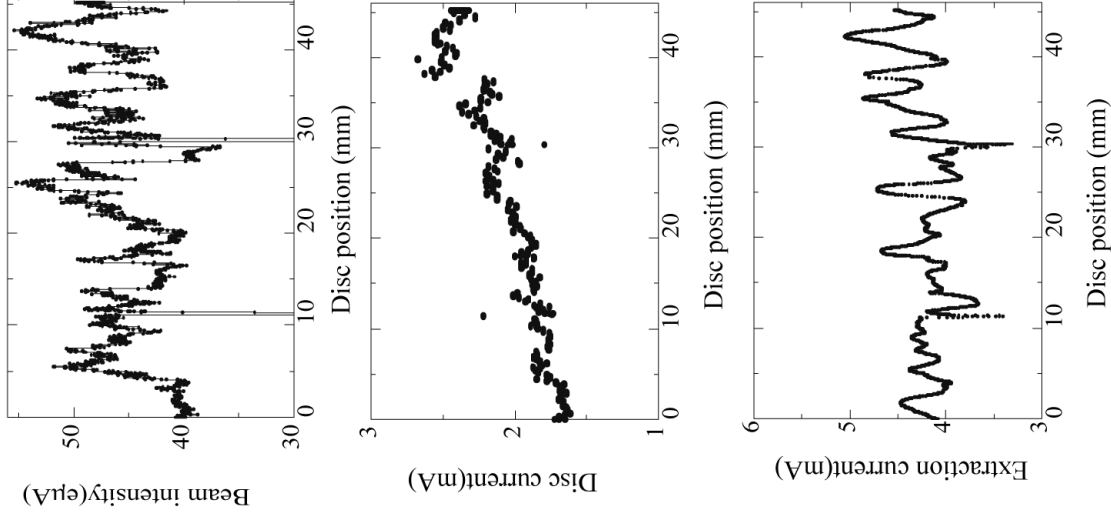
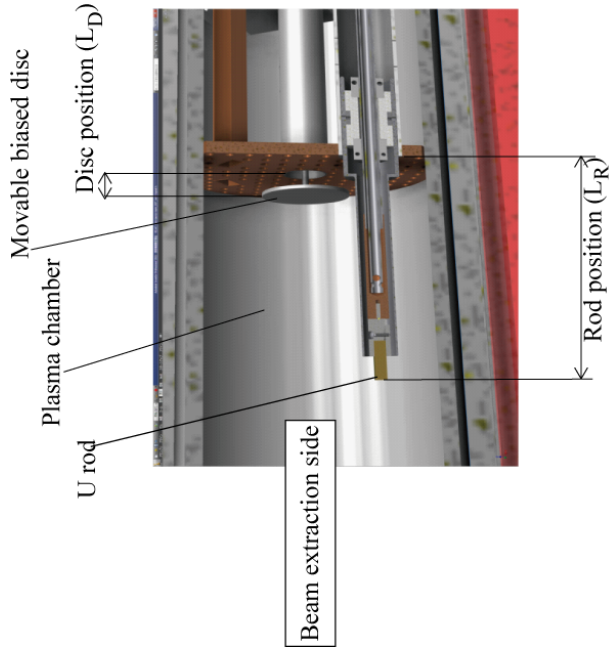
(U^{33+} **80eμA@2kW**)

Sputtering rod position and Voltage

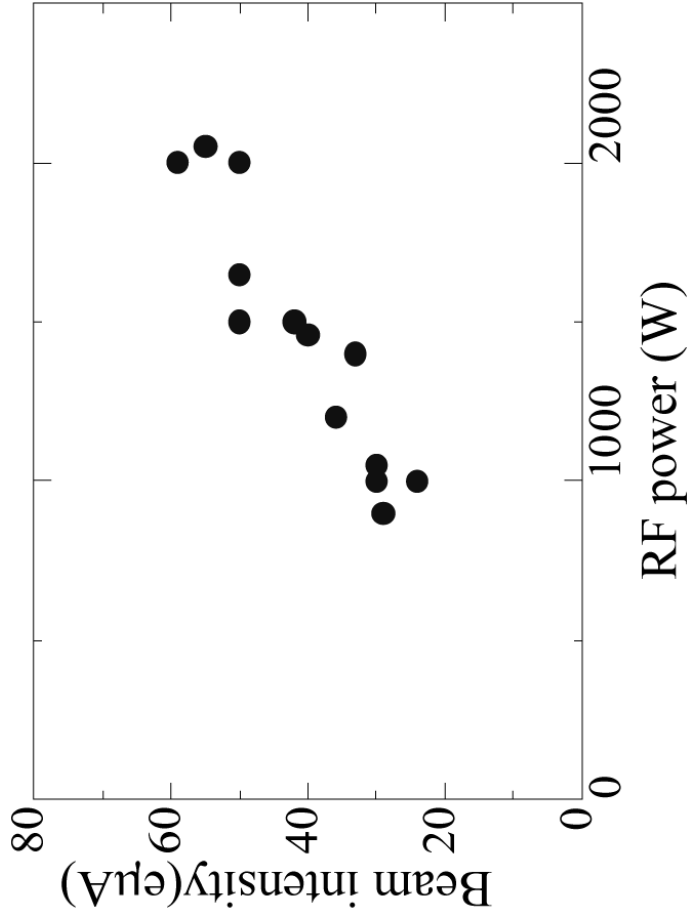


Bias disk position effect

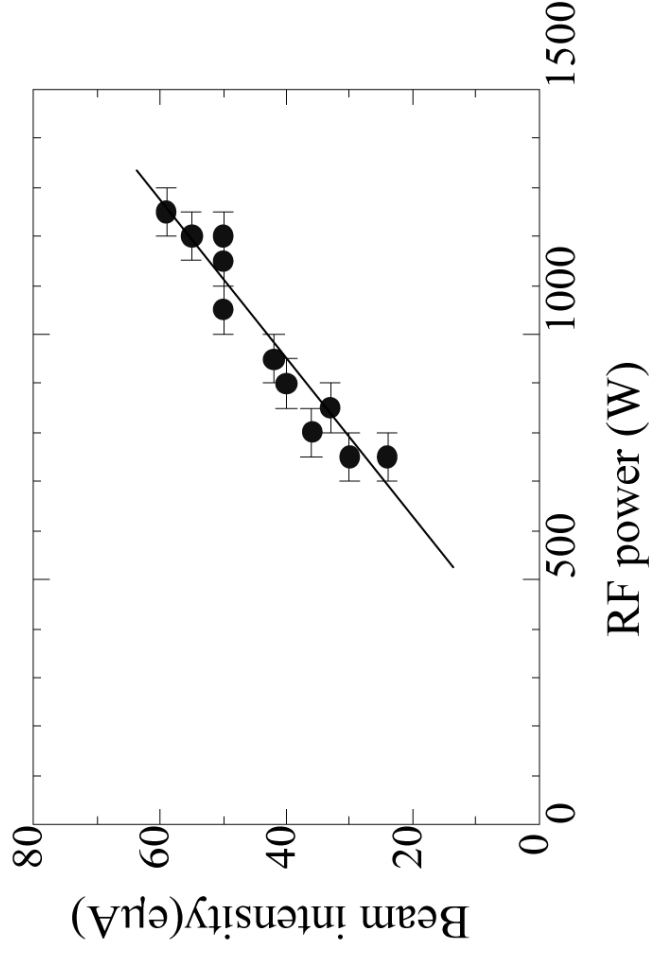
201201231602



U³⁵⁺ beam intensity VS RF power



Diode output

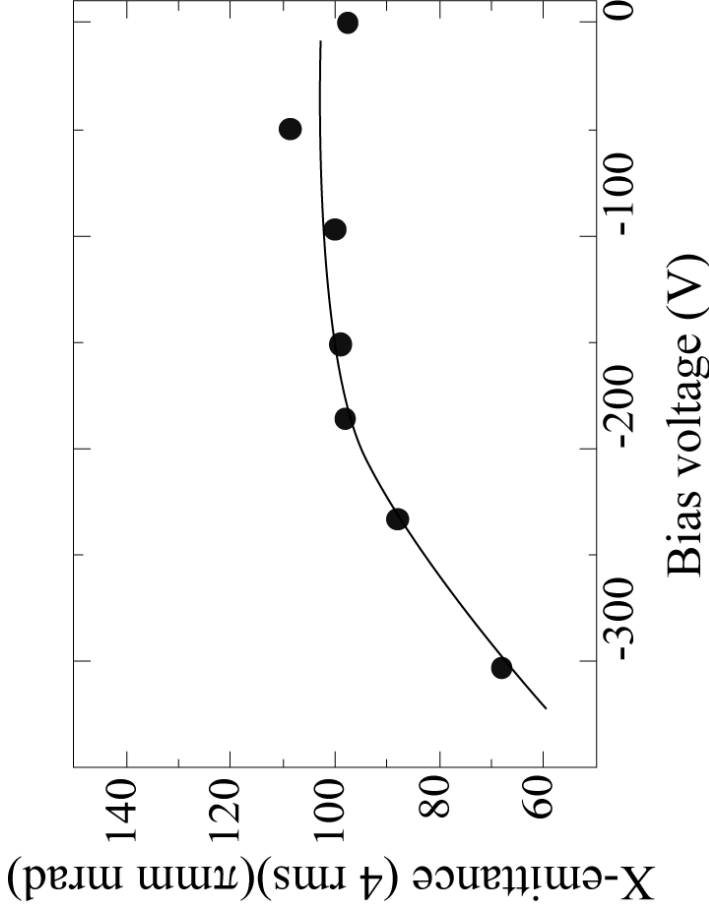


Calculate from plasma chamber
cooling water temperature

Injected RF power efficiency to Plasma chamber is about 60~70%

Emittance

□ U^{35+} beam
emittance
 $\sim 100\pi$ mm mrad



U^{35+} X-emittance as a function of Bias disk voltage

K. Ozeki et al., Poster WEPP08

Summary (Xe and U ion beam)

Beam intensity

▣ Xe²⁵⁺ 250eμA @1.7kW(28GHz)

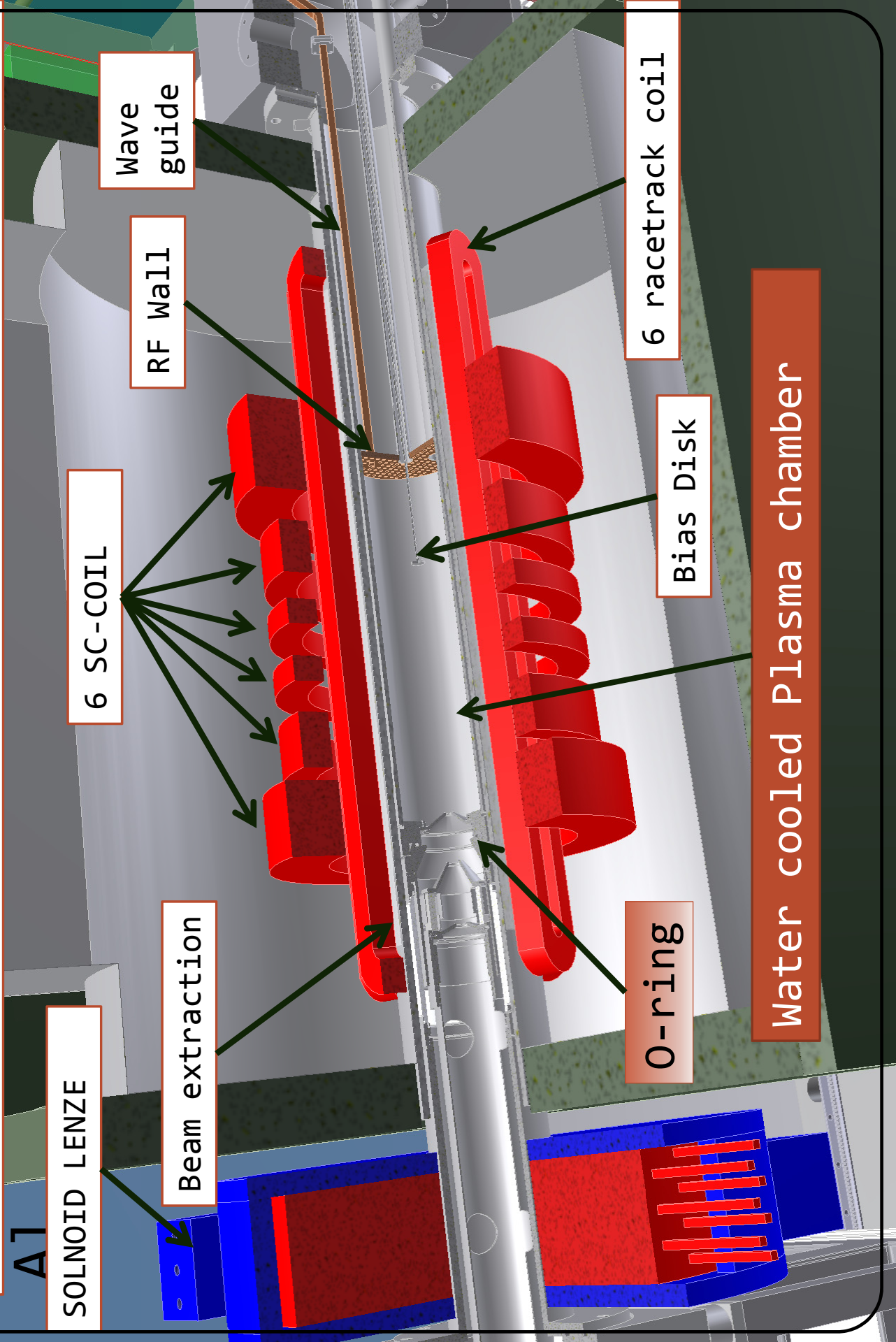
▣ U³⁵⁺ 60eμA @ 2 kW(28GHz)

U³³⁺ 80eμA @ 2 kW(28GHz)

(20 times from RIKEN 18GHz ECRIS)

▣ Emittance ~100π mm mrad

Plasma chamber replaced From SUS to



SOLNOID LENZE

Beam extraction

6 SC-COIL

RF Wall

Wave
guide

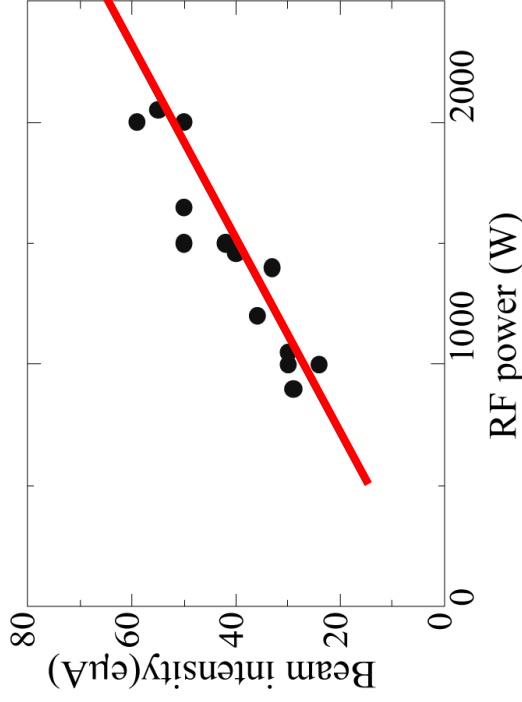
O-ring

Bias Disk

6 racetrack coil

Water cooled Plasma chamber

High temperature oven



RF power >6kW

$U^{35+} \sim 200 \mu A$

using High temp. Oven

more U vapour



- Power consumption for the oven was improved about 80 % (1.6 [kW] → 350 [W]) by using a method of a connection by the different kind metal
- Non-trouble during about 270 hours at 1800 ~ 2000 °C (without sample)
- Long-term stability, durability, control, and reproducibility were confirmed.

D. Leitner et al, RSI 79(2008)02C710

Conclusion and future plan

- Now AI Plasma chamber is under commissioning. High RF power result will be coming soon.
- To produce U vapour, we will make a test experiment with high temperature oven.
- More Optimization of the Magnetic field distribution.

Final goal is $U^{35+} > 200 \mu A$

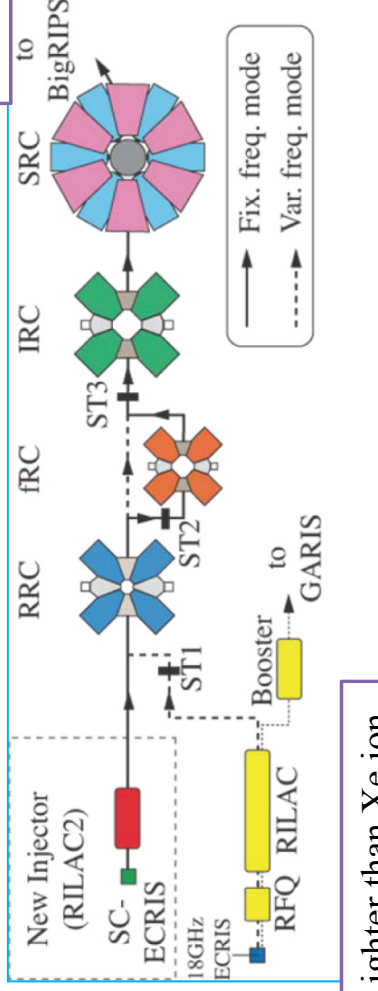
The background is a vibrant green with a crinkled, paper-like texture. It is adorned with bold, expressive white and black brushstrokes that sweep across the frame, creating a sense of movement and depth. The white strokes are more numerous and varied in thickness, while the black strokes are fewer but more prominent, often following the same general direction as the white ones.

Thank you for your attention

RIKEN RIBF

Heavier than Xe ion

$\sim 345 \text{ MeV/u}$



18GHz ECR ion source

Lighter than Xe ion

RILAC

28GHz SC-ECRIS

RILAC II

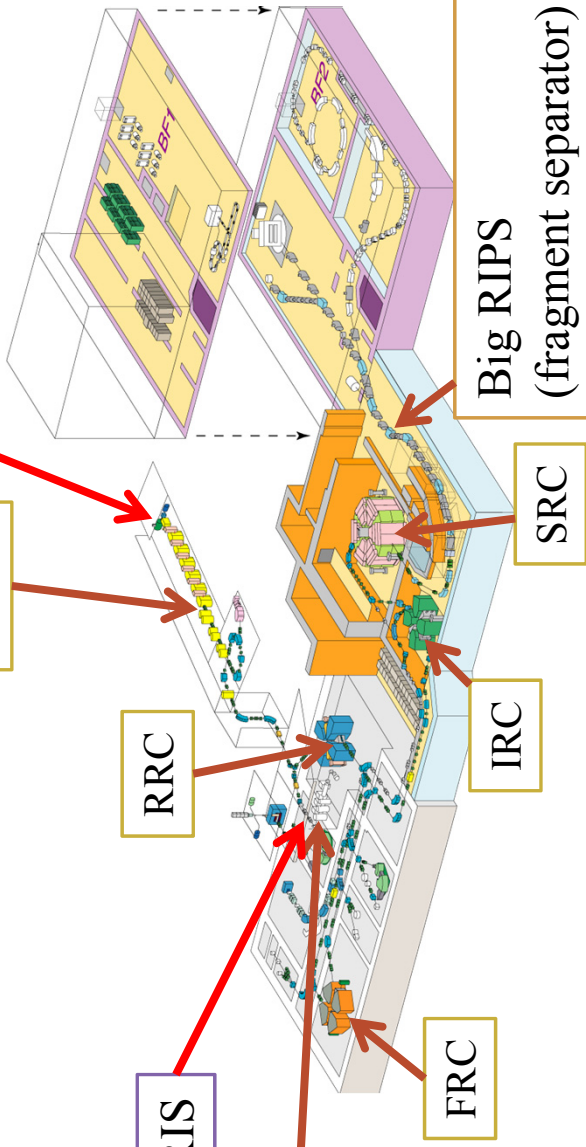
RRC

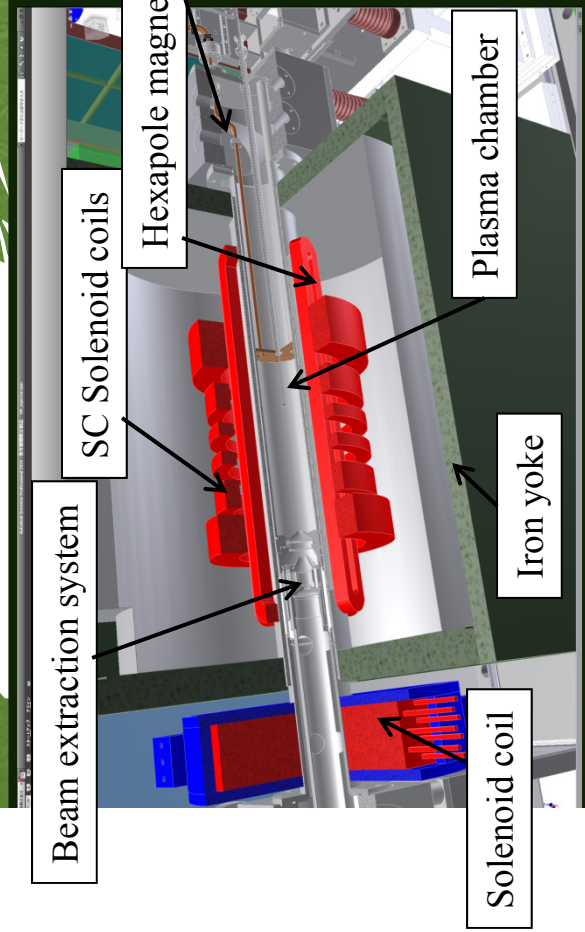
Big RIPS
(fragment separator)

SRC

IRC

FRC

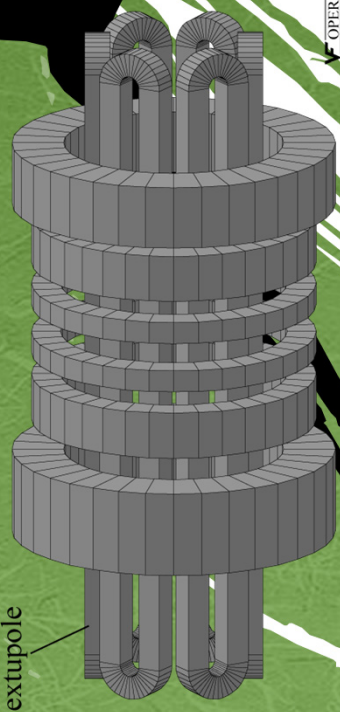




Microwave guide

SL1 SL2 SL3 SL4 SL5 SL6

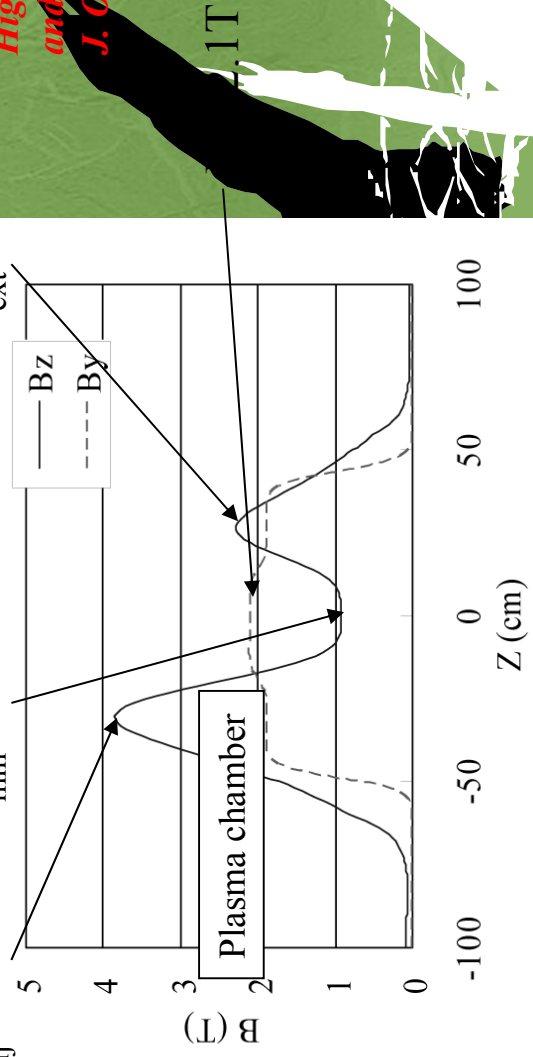
Sextupole

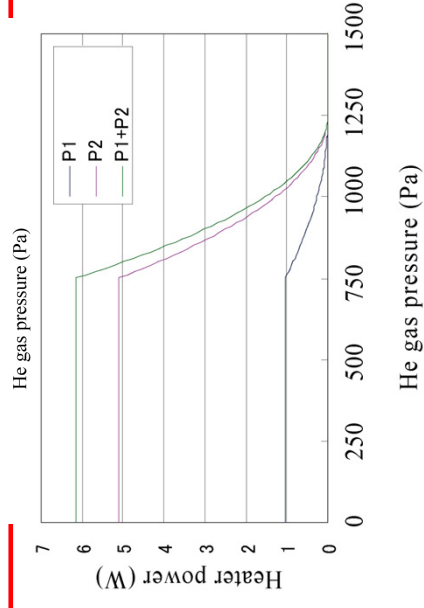
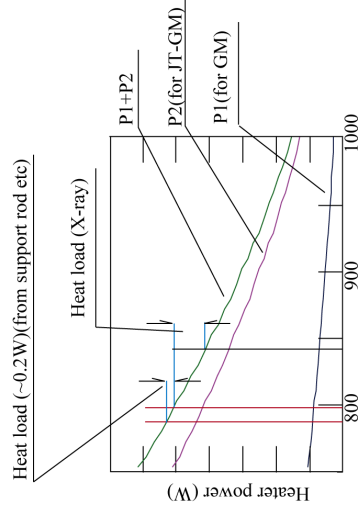
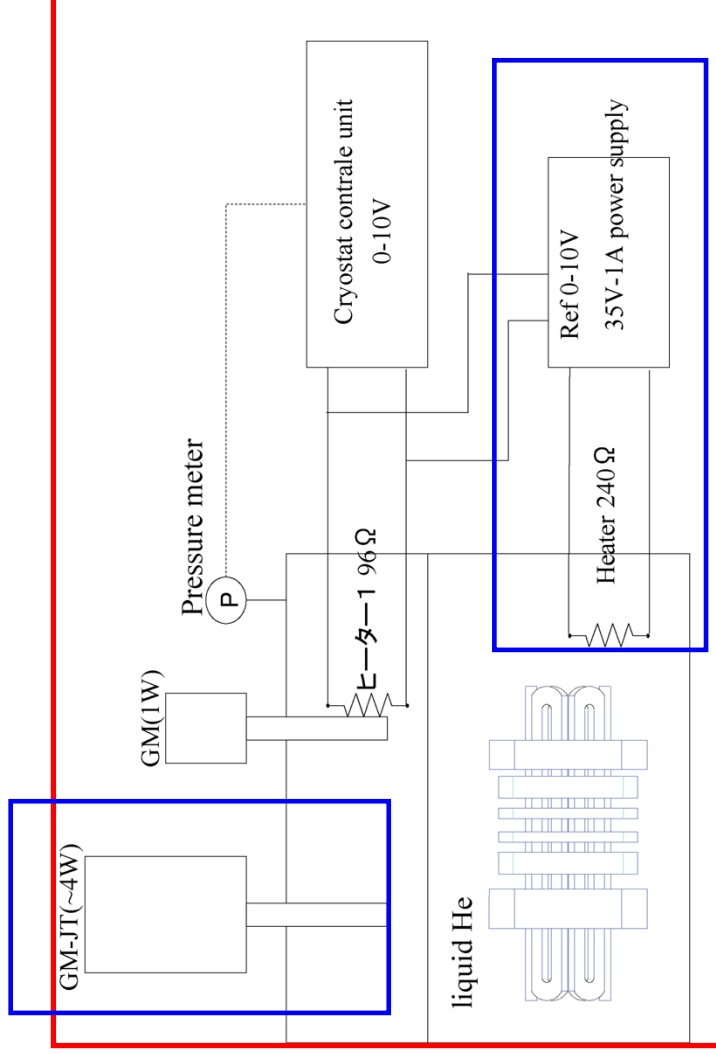


For 28GHz operations

$B_{inj} \sim 3.8T$ $B_{min} < 1.0T$ $B_{ext} \sim 2.3T$

High energy Physics
and Nuclear Physics 31(2007)37
J. Ohnishi et al,





Sputtering Voltage

